

DEPOSITION SYSTEMS FOR COMPOUND SEMICONDUCTORS

AIX 2800G4-TM

for GaAs/InP based Optoelectronics and p-HEMT/HBT Devices

AIXTRON
Our technology. Your future.

Increase your capacity and take advantage of highest Yield

AIX 2800G4-TM MOCVD System

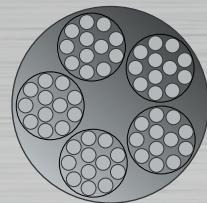
Your Benefit

- ▶ Highest device yield & throughput
- ▶ High precursor & hydride efficencies
- ▶ Lowest cost/wafer
- ▶ Flexible configuration for 2 to 8 inch

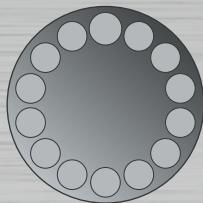
Design Highlights

- ▶ Automated satellite loading
- ▶ Triple gas injector
- ▶ Latest reactor design featuring
 - Advanced process tuning
 - Increased process robustness
 - Minimized overall maintenance

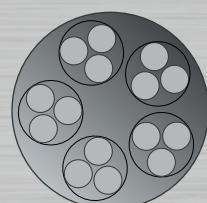
Available Susceptor Configurations



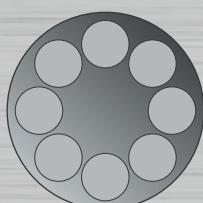
60x2 inch



14x3 inch



15x4 inch

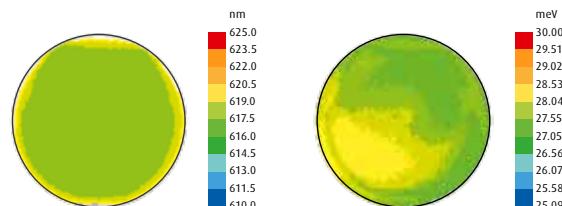


8x6 inch

Process and Transfer Module



4 inch ALGaInP MQW results



PL wavelength uniformity (Avg. 617nm)

0.6 nm standard deviation without EE

FHWM uniformity (Avg. 27meV)

1.7 % standard deviation without EE



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